

Reply under 37 C.F.R. 1.116  
Expedited Procedure  
Technology Center 2823

Confirmation No. 6408

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Meunier-Beillard <i>et al.</i>	Examiner:	Khiem Nguyen
Serial No.:	10/550,853	Group Art Unit:	2823
Filed:	September 22, 2005	Docket No.:	NL030357 US1
Title:	METHOD OF EPITAXIAL DEPOSITION OF AN N-DOPED SILICON LAYER		

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FINAL OFFICE ACTION RESPONSE

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Customer No.

**65913**

Dear Sir:

In response to the final Office Action dated September 17, 2007, please reconsider the application in view of the following amendments and remarks.

A complete listing of the claims, to include any amendments presented therein, begins on page 2 of this paper.

Remarks/Arguments follow on page 5.

**Authorization is provided to charge/credit Deposit Account 50-0996 (NXPS.265PA)** any requisite fees/overages to enter this paper.